

Most frequently occurring classifications of patents returned
from a search of 10525136 on Mar 15 , 2007

Original Classifications

2 315/111.21
2 378/122
2 250/214.1
2 315/326

Cross-Reference Classifications

4 315/111.81
4 313/609
3 315/111.21
3 315/111.31
3 313/607
3 313/634
2 118/620
2 216/79
2 257/E21.279
2 427/578
2 257/E21.293
2 378/119
2 315/111.71
2 378/122
2 378/136
2 372/87
2 204/298.36
2 428/446
2 313/234
2 257/E31.017
2 257/E31.021
2 257/E31.093
2 313/619
2 313/632
2 250/423R
2 315/344
2 315/246

Combined Classifications

5 315/111.21
5 315/111.81
4 378/122
4 313/609
4 313/634
3 378/119
3 315/111.31
3 313/607
2 118/50.1
2 118/620
2 216/79
2 257/E21.279
2 427/578
2 257/E21.293
2 315/111.71
2 378/34
2 378/136
2 372/86
2 372/87
2 204/298.36
2 428/446
2 313/485
2 313/234

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2 315/248
2 134/1.1
2 216/67
2 427/570
2 313/493
2 250/214.1
2 257/E31.017
2 257/E31.021
2 257/E31.093
2 313/619
2 313/632
2 250/423R
2 315/111.41
2 313/484
2 313/490
2 315/326
2 315/344
2 315/246

Titles of most frequently occurring classifications of patents returned
from a search of 10525136 on Mar 15 , 2007

5 315/111.21 (2 OR, 3 XR)
Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
315/111.01 .DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE
DISCHARGE SPACE
315/111.21 ..Plasma generating

5 315/111.81 (1 OR, 4 XR)
Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
315/111.01 .DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE
DISCHARGE SPACE
315/111.81 ..Electron or ion source

4 378/122 (2 OR, 2 XR)
Class 378 X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/119 .SOURCE
378/121 ..Electron tube
378/122 ...Field emission or cold cathode

4 313/609 (0 OR, 4 XR)
Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES
313/567 .WITH GAS OR VAPOR
313/609 ..Having baffle, partition, or constricting means affecting
discharge

4 313/634 (1 OR, 3 XR)
Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES
313/567 .WITH GAS OR VAPOR
313/634 ..Envelope with particular structure

3 378/119 (1 OR, 2 XR)
Class 378 X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/119 .SOURCE

3 315/111.31 (0 OR, 3 XR)
Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
315/111.01 .DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE
DISCHARGE SPACE
315/111.21 ..Plasma generating
315/111.31 ...With extraction electrode

3 313/607 (0 OR, 3 XR)
Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES
313/567 .WITH GAS OR VAPOR
313/607 ..Having electrode exterior to envelope

2 118/50.1 (1 OR, 1 XR)
Class 118 COATING APPARATUS
118/50 .WITH VACUUM OR FLUID PRESSURE CHAMBER
118/50.1 ..With means to apply electrical and/or radiant energy to
work and/or coating material

2 118/620 (0 OR, 2 XR)
Class 118 COATING APPARATUS
118/620 .WITH MEANS TO APPLY ELECTRICAL AND/OR RADIANT ENERGY TO
WORK AND/OR COATING MATERIAL

2 216/79 (0 OR, 2 XR)
Class 216 ETCHING A SUBSTRATE: PROCESSES
216/58 .GAS PHASE ETCHING OF SUBSTRATE

216/74 ..Etching inorganic substrate
 216/79 ...Etching silicon containing substrate

2 257/E21.279 (0 OR, 2 XR)
 Class 257 ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE DIODES)
 257/E21.001 .PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF PARTS THEREOF (EPO)
 257/E21.002 ..Manufacture or treatment of semiconductor device (EPO)
 257/E21.04 ...Device having at least one potential-jump barrier or surface barrier, e.g., PN junction, depletion layer, carrier concentration layer (EPO)
 257/E21.085Device having semiconductor body comprising Group IV elements or Group III-V compounds with or without impurities, e.g., doping materials (EPO)
 257/E21.211Treatment of semiconductor body using process other than deposition of semiconductor material on a substrate, diffusion or alloying of impurity material, or radiation treatment (EPO)
 257/E21.214To change their surface-physical characteristics or shape, e.g., etching, polishing, cutting (EPO)
 257/E21.24To form insulating layer thereon, e.g., for masking or by using photolithographic technique (EPO)
 257/E21.266Inorganic layer (EPO)
 257/E21.271Composed of oxide or glassy oxide or oxide based glass (EPO)
 257/E21.274Deposition from gas or vapor (EPO)
 257/E21.278Deposition of silicon oxide (EPO)
 257/E21.279On silicon body (EPO)

2 427/578 (0 OR, 2 XR)
 Class 427 COATING PROCESSES
 427/457 .DIRECT APPLICATION OF ELECTRICAL, MAGNETIC, WAVE, OR PARTICULATE ENERGY
 427/569 ..Plasma (e.g., corona, glow discharge, cold plasma, etc.)
 427/578 ...Silicon containing coating material

2 257/E21.293 (0 OR, 2 XR)
 Class 257 ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE DIODES)
 257/E21.001 .PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF PARTS THEREOF (EPO)
 257/E21.002 ..Manufacture or treatment of semiconductor device (EPO)
 257/E21.04 ...Device having at least one potential-jump barrier or surface barrier, e.g., PN junction, depletion layer, carrier concentration layer (EPO)
 257/E21.085Device having semiconductor body comprising Group IV elements or Group III-V compounds with or without impurities, e.g., doping materials (EPO)
 257/E21.211Treatment of semiconductor body using process other than deposition of semiconductor material on a substrate, diffusion or alloying of impurity material, or radiation treatment (EPO)
 257/E21.214To change their surface-physical characteristics or shape, e.g., etching, polishing, cutting (EPO)
 257/E21.24To form insulating layer thereon, e.g., for masking or by using photolithographic technique (EPO)
 257/E21.266Inorganic layer (EPO)
 257/E21.292Inorganic layer composed of nitride (EPO)
 257/E21.293Of silicon nitride (EPO)

2 315/111.71 (0 OR, 2 XR)
 Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
 315/111.01 .DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE DISCHARGE SPACE

315/111.21 ..Plasma generating
 315/111.41 ...With magnetic field
 315/111.71Plasma containment

2 378/34 (1 OR, 1 XR)

Class 378 X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
 378/1 .SPECIFIC APPLICATION
 378/34 ..Lithography

2 378/136 (0 OR, 2 XR)

Class 378 X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
 378/119 .SOURCE
 378/121 ..Electron tube
 378/136 ...With specific cathode

2 372/86 (1 OR, 1 XR)

Class 372 COHERENT LIGHT GENERATORS
 372/69 .PARTICULAR PUMPING MEANS
 372/81 ..Electrical
 372/86 ...Having an auxiliary ionization means

2 372/87 (0 OR, 2 XR)

Class 372 COHERENT LIGHT GENERATORS
 372/69 .PARTICULAR PUMPING MEANS
 372/81 ..Electrical
 372/87 ...Having particular electrode structure

2 204/298.36 (0 OR, 2 XR)

Class 204 CHEMISTRY: ELECTRICAL AND WAVE ENERGY
 204/193 .APPARATUS
 204/298.01 ..Coating, forming or etching by sputtering
 204/298.31 ...Etching
 204/298.36Beam or directed flux etching (e.g., ion beam, etc.)

2 428/446 (0 OR, 2 XR)

Class 428 STOCK MATERIAL OR MISCELLANEOUS ARTICLES
 428/411.1 .COMPOSITE (NONSTRUCTURAL LAMINATE)
 428/446 ..Of silicon containing (not as silicon alloy)

2 313/485 (1 OR, 1 XR)

Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES
 313/483 .WITH LUMINESCENT SOLID OR LIQUID MATERIAL
 313/484 ..With gaseous discharge medium
 313/485 ...Phosphor on envelope wall

2 313/234 (0 OR, 2 XR)

Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES
 313/234 .ELECTRODE EXTERIOR TO ENVELOPE

2 315/248 (1 OR, 1 XR)

Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
 315/246 .PULSATING OR A.C. SUPPLY
 315/248 ..Induction-type discharge device load

2 134/1.1 (1 OR, 1 XR)

Class 134 CLEANING AND LIQUID CONTACT WITH SOLIDS
 134/1**1 .PROCESSES
 134/1 ..Including application of electrical radiant or wave energy

to work

134/1.1 ...Plasma cleaning

2 216/67 (1 OR, 1 XR)

Class 216 ETCHING A SUBSTRATE: PROCESSES

216/58 .GAS PHASE ETCHING OF SUBSTRATE
 216/63 ..Application of energy to the gaseous etchant or to the
 substrate being etched
 216/67 ...Using plasma

2 427/570 (1 OR, 1 XR)
 Class 427 COATING PROCESSES
 427/457 .DIRECT APPLICATION OF ELECTRICAL, MAGNETIC, WAVE, OR
 PARTICULATE ENERGY
 427/569 ..Plasma (e.g., corona, glow discharge, cold plasma, etc.)
 427/570 ...Utilizing plasma with other nonionizing energy sources

2 313/493 (1 OR, 1 XR)
 Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES
 313/483 .WITH LUMINESCENT SOLID OR LIQUID MATERIAL
 313/484 ..With gaseous discharge medium
 313/485 ...Phosphor on envelope wall
 313/493Envelope structure or material

2 250/214.1 (2 OR, 0 XR)
 Class 250 RADIANT ENERGY
 250/200 .PHOTOCELLS; CIRCUITS AND APPARATUS
 250/206 ..Photocell controlled circuit
 250/214R ...Special photocell or electron tube circuits
 250/214.1Special photocell

2 257/E31.017 (0 OR, 2 XR)
 Class 257 ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE
 DIODES)
 257/E31.001 .SEMICONDUCTOR DEVICES RESPONSIVE OR SENSITIVE TO
 ELECTROMAGNETIC RADIATION (E.G., INFRARED RADIATION, ADAPTED FOR CONVERSION OF
 RADIATION INTO ELECTRICAL ENERGY OR FOR CONTROL OF ELECTRICAL ENERGY BY SUCH
 RADIATION PROCESSES, OR APPARATUS PECULIAR TO MANUFACTURE OR TREATMENT OF SUCH
 DEVICES, OR OF PARTS THEREOF) (EPO)
 257/E31.002 ..Characterized by semiconductor body (EPO)
 257/E31.003 ...Characterized by semiconductor body material (EPO)
 257/E31.004Inorganic materials (EPO)
 257/E31.015Including, apart from doping material or other
 impurity, only Group II-VI compound (e.g., CdS, ZnS, HgCdTe) (EPO)
 257/E31.016For device having potential or surface barrier (EPO)
 257/E31.017Characterized by doping material (EPO)

2 257/E31.021 (0 OR, 2 XR)
 Class 257 ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE
 DIODES)
 257/E31.001 .SEMICONDUCTOR DEVICES RESPONSIVE OR SENSITIVE TO
 ELECTROMAGNETIC RADIATION (E.G., INFRARED RADIATION, ADAPTED FOR CONVERSION OF
 RADIATION INTO ELECTRICAL ENERGY OR FOR CONTROL OF ELECTRICAL ENERGY BY SUCH
 RADIATION PROCESSES, OR APPARATUS PECULIAR TO MANUFACTURE OR TREATMENT OF SUCH
 DEVICES, OR OF PARTS THEREOF) (EPO)
 257/E31.002 ..Characterized by semiconductor body (EPO)
 257/E31.003 ...Characterized by semiconductor body material (EPO)
 257/E31.004Inorganic materials (EPO)
 257/E31.019Including, apart from doping material or other
 impurity, only Group III-V compound (EPO)
 257/E31.02For device having potential or surface barrier (EPO)
 257/E31.021Characterized by doping material GaAlAs, InGaAs,
 InGaAsP (EPO)

2 257/E31.093 (0 OR, 2 XR)
 Class 257 ACTIVE SOLID-STATE DEVICES (E.G., TRANSISTORS, SOLID-STATE
 DIODES)
 257/E31.001 .SEMICONDUCTOR DEVICES RESPONSIVE OR SENSITIVE TO

ELECTROMAGNETIC RADIATION (E.G., INFRARED RADIATION, ADAPTED FOR CONVERSION OF RADIATION INTO ELECTRICAL ENERGY OR FOR CONTROL OF ELECTRICAL ENERGY BY SUCH RADIATION PROCESSES, OR APPARATUS PECULIAR TO MANUFACTURE OR TREATMENT OF SUCH DEVICES, OR OF PARTS THEREOF) (EPO)

257/E31.052 ..Adapted to control current flow through device (e.g., photoresistor) (EPO)

257/E31.093 ...Device sensitive to infrared, visible, or ultraviolet radiation (EPO)

2 313/619 (0 OR, 2 XR)

Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES

313/567 .WITH GAS OR VAPOR

313/619 ..Negative or cathode glow device

2 313/632 (0 OR, 2 XR)

Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES

313/567 .WITH GAS OR VAPOR

313/631 ..Having particular electrode structure

313/632 ...Cathode or anode

2 250/423R (0 OR, 2 XR)

Class 250 RADIANT ENERGY

250/423R .ION GENERATION

2 315/111.41 (1 OR, 1 XR)

Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

DISCHARGE SPACE 315/111.01 .DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE

315/111.21 ..Plasma generating

315/111.41 ...With magnetic field

2 313/484 (1 OR, 1 XR)

Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES

313/483 .WITH LUMINESCENT SOLID OR LIQUID MATERIAL

313/484 ..With gaseous discharge medium

2 313/490 (1 OR, 1 XR)

Class 313 ELECTRIC LAMP AND DISCHARGE DEVICES

313/483 .WITH LUMINESCENT SOLID OR LIQUID MATERIAL

313/484 ..With gaseous discharge medium

313/485 ...Phosphor on envelope wall

313/490With amalgam

2 315/326 (2 OR, 0 XR)

Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/326 .DISCHARGE DEVICE LOAD

2 315/344 (0 OR, 2 XR)

Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/326 .DISCHARGE DEVICE LOAD

315/344 ..Electromagnetic influenced discharge device

2 315/246 (0 OR, 2 XR)

Class 315 ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/246 .PULSATING OR A.C. SUPPLY